

# Call for papers

## DPS2008

### 30th International Symposium on Dry Process

November 26-28, 2008

KOKUYO HALL, Minato-ku, Tokyo JAPAN

<http://www.kokuyo.co.jp/showroom/hall/access/>

**Sponsored by** The Japan Society of Applied Physics  
**In conjunction with** The Institute of Electronics, Information and Communication Engineers of Japan  
(tentative) The Korean Institute of Surface Engineering, The Korean Vacuum Society  
The Electrochemical Society of Japan, Electrochemical Society Japan Chapter

Dry processes are the state of the art technologies leading the way through ultra-high performance in microelectronic devices. The DPS provides for 30 years a valuable forum of discussions on science and technology of new developments in this field. Present 30th symposium is to be held in Tokyo, Japan. A special issue of "Japanese Journal of Applied Physics" will be published besides the Extended Abstracts.

The DPS Organizing Committee invites you to the conference and welcomes the submission of your papers.

#### General Topics and Arranged Session

**Theme:** Dry processes and related technologies from fundamentals to applications

**Topics:** Mechanisms of plasma-induced surface reactions / Diagnostics and monitoring of plasmas and Reaction surfaces / Damages induced by photon-, electron-, and ion-irradiation onto surface / Surface reactions of wet process (cleaning, CMP, electroplating) / Process technologies for etching, CVD and surface treatment / Dry process for low-k, high-k, and new materials / MEMS technologies / Process technologies for flat panel display (LCD, PDP, Organic ELD) / Nanotechnologies and bio-applications / Environmental technologies / Equipment technology for dry processes / New dry process concept (micro-plasmas, atmospheric plasmas, etc)

**Arranged Session:** "Fluctuation, DFM, FDC, and uniformity of dry process"; Contributed papers related to this session title will be arranged and discussed emphatically as the latest topic.

#### Submission of Extended Abstracts

Two page (A4) camera-ready abstract, including figures and references, should be submitted by **July 13, 2008**. After the reviewing process, authors will be notified of acceptance or rejection of their abstracts by *September 1, 2008*. Based on scientific quality the Program Committee will select about 20 papers for oral presentation. Accepted contributions will appear on the DPS 2008 Extended Abstract.

#### Special Issue of "Japanese Journal of Applied Physics (JJAP)"

All participants willing to submit papers to the special issue should hand in the manuscripts at the registration desk on the first day of the symposium. All manuscripts will be reviewed by standard procedures of peer-review. The accepted papers will be published in a special issue of "JJAP".

#### Invited Speakers

"Evolutionary Trend of Silicon Nanoelectronics and Beyond CMOS Devices", Toshiro Hiramoto (Univ. Tokyo)

"Etch Process Control for Advanced Logic Development (tentative)", Richard Wise (IBM)

"Reaction mechanisms during plasma-assisted ALD of metals and high-k oxides", W.M.M. Kessels (TU/e)

"Metallic vs Organic Mask Strategies on Etch and Ash Processes for Porous Low-k Materials (tentative)", Thierry Chevolleau (CEA-Leti)

"GeOxNy Interfacial Layer for High-k/Ge Gate stack: Chemical States and Electrical Correlations", Yasuhiro Oshima (Stanford Univ., TEL-US)

"Organic Semiconductor by Liquid Crystalline Molecules (tentative)", Junichi Hanna (Tokyo Inst. Tech.)

#### Registration Fee

The registration fee covers the Conference Abstracts with CD-ROM: Early registration (before October 12, 2008): 35,000 JPY for society member, 40,000 JPY for non-member and 8,000 JPY for student.

Late registration: 38,000 JPY for society member, 43,000 JPY for non-member and 8,000 JPY for student.

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